11/10
5/18/03
D. Bell

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Yamazaki, et al. Art Unit: 2881
Serial No.: 09/696,863 Examiner: Nikita Wells
Filed : October 25, 2000 Confirmation No.: 2608
Title : APPARATUS AND METHOD FOR DOPING

Commissioner for Patents
Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicants call attention to the attached Information Disclosure Statement and documents listed on form PTO-1449.

This filing is being made with an RCE. No fee is required.

English-language abstracts are provided where available. Concise explanations are provided for the following references:

AM: JP 64-001455 discloses an ion source called Freeman type ion source, and discloses the extraction electrodes 10 and 12 each having slits 10s and 12s for extracting an ion beam 14 are provided in front of a slit 2s of a plasma generation chamber 2. Further, when an ion source gas or a metal steam is introduced into the plasma generation chamber 2 from holes 2a or 2b, respectively, an arc discharge is generated between a

CERTIFICATE OF MAILING BY FIRST CLASS MAIL

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and is addressed to the Commissioner for Patents, Washington, D.C. 20231.

April 23, 2003
Date of Deposit

R. P. Ippolito
Signature

Roxanne Ippolito
Typed or Printed Name of Person Signing Certificate

filament 4 and the plasma generation chamber 2, and the ion beam 14 is extracted through the slits 2s, 10s and 12s.

The opponent asserts that each slit 2s, 10s and 12s has a rectangular shape, so that the ion beam 14 having a rectangular cross section is extracted.

AN: JP 06-060099 discloses an accelerating tube, and discloses that an ion beam 2 is accelerated through acceleration electrodes 4a-4c.

AO: M. Naito's article discloses an ion implantation apparatus using Freeman type ion source. The ion implantation apparatus has an electromagnet for a mass spectrometry. A mass analyzed ion beam passes a filter electrode and enters an acceleration tube for being accelerated to a required energy. A sample is put on a platen, and the platen, and the platen is driven at a speed corresponding to a beam amount by a servomotor, so that uniformity of the implantation is improved along the moving direction.

AP: N. Nagai's article discloses a parallel ion implantation apparatus using a collimator magnet. The collimator magnet is an electromagnet which generates a static magnetic field and bends a swept beam to form a parallel beam.

Consideration of the foregoing and enclosures plus the return of a copy of the enclosed form PTO-1449 with the

Examiner's initials in the left column per MPEP 609 are earnestly solicited along with an early action on the merits.

Please apply any additional charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Date: 04/23/03

Scott C. Harris
Reg. No. 32,030

Fish & Richardson P.C.
Customer Number: 20985 *  *
4350 La Jolla Village Drive, Suite 500
San Diego, California 92122
Telephone: (858) 678-5070
Facsimile: (858) 678-5099

10262726.doc